CLAIM AMENDMENTS

- 1. (Currently Amended) A semiconductor laser device comprising: an active layer;
- a lower clad <u>cladding</u> layer located below <u>on a first side of</u> said active layer;
- a first upper elad cladding layer located above on a second side of said active layer the second side being on a side of the active layer;

an etching stopper layer located above opposite said first upper elad cladding layer on the first side of said active layer; and

a second upper elad cladding layer located above opposite said etching stopper layer, on the first side of said active layer, and provided with including a stripe-form protrusion, in which a stripe-form light-guiding channel is formed-below located, between said protrusion and said etching stopper layer, wherein said etching stopper layer is formed as a single layer and is composed of a material different from a material materials of each of said elad lower, first upper, and second upper cladding layers, and has a refractive index nearly equal to a refractive index of each of said elad lower, first upper, and second upper cladding layers.

- 2. (Currently Amended) The semiconductor laser device according to claim 1, wherein said active layer contains GaInP, each of said elad lower, first upper, and second upper cladding layers contains Contains AlGaInP, and said etching stopper layer contains $Al_xGa_{1-x}As$ -of arbitrary Al composition ratio x, where $0 \le x \le 1$.
- 3. (Currently Amended) The semiconductor laser device according to claim 2, wherein said Al composition ratio x is larger than or equal to at least 0.45.
 - 4. (Currently Amended) A semiconductor laser device comprising: an active layer;
 - a lower elad cladding layer located below on a first side of said active layer;
- a first upper elad cladding layer located above on a second side of said active layer, the second side being on a side of the active layer; and
- a second upper elad <u>cladding</u> layer located <u>above opposite</u> said first upper elad <u>cladding</u> layer, on the second side of said active layer, and provided with including a stripe-form protrusion, in which a stripe-form light-guiding channel is formed below <u>located</u>, <u>between</u> said protrusion <u>and said second upper cladding layer</u>, wherein said second upper <u>cladding</u> layer is composed of a material different from a material of said first upper clad

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<u>cladding</u> layer, and has a refractive index nearly equal to a refractive index of said first upper <u>elad</u> <u>cladding</u> layer.

- 5. (Currently Amended) The semiconductor laser device according to claim 4, wherein said active layer contains GaInP, each of said lower elad cladding layer and said first upper elad cladding layer containing contains AlGaInP, and said second upper clad layer containing contains $Al_xGa_{1-x}As$ of arbitrary Al composition ratio x where $0 \le x \le 1$.
- 6. (Currently Amended) The semiconductor laser device according to claim 5, wherein said Al-composition ratio x is larger than or equal to at least 0.45.